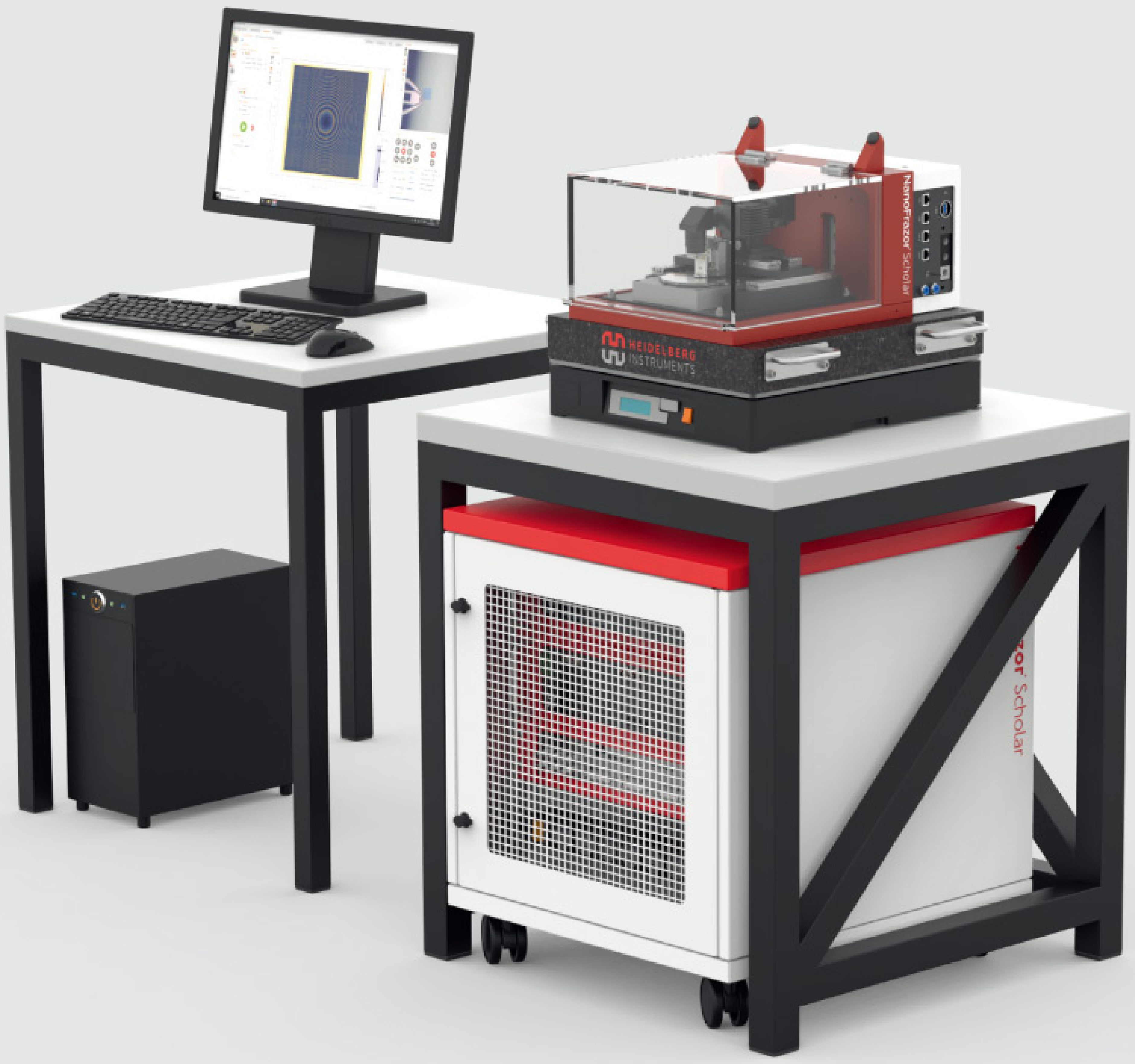
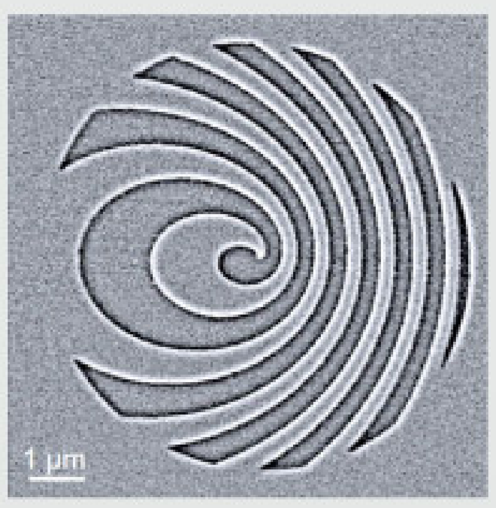
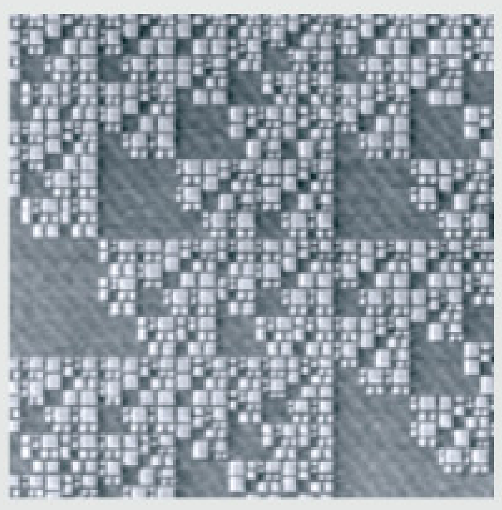
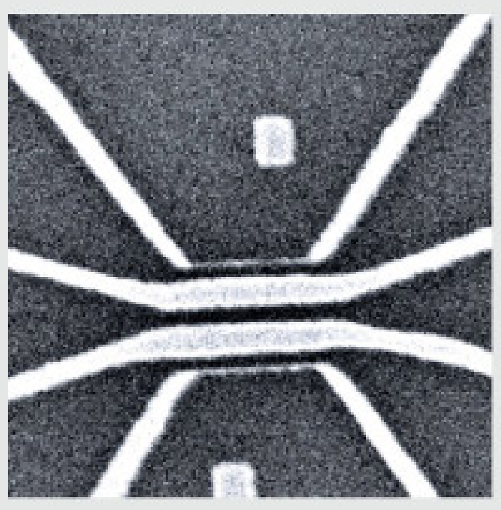
# NanoFrazor® Scholar

## ADVANCED NANOLITHOGRAPHY FOR EVERYONE



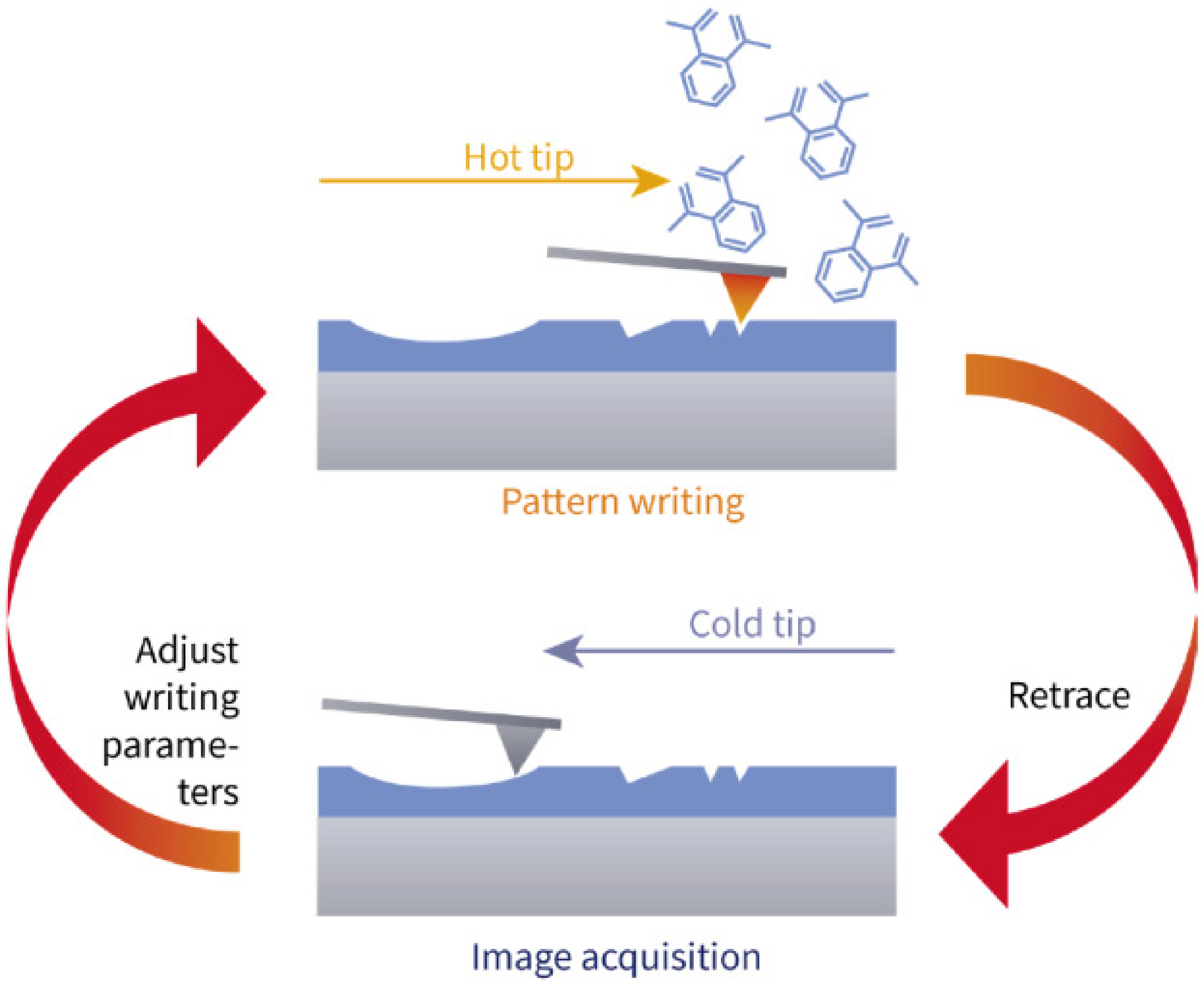


# NanoFrazor® Scholar

## TABLETOP DIRECT WRITE NANOLITHOGRAPHY

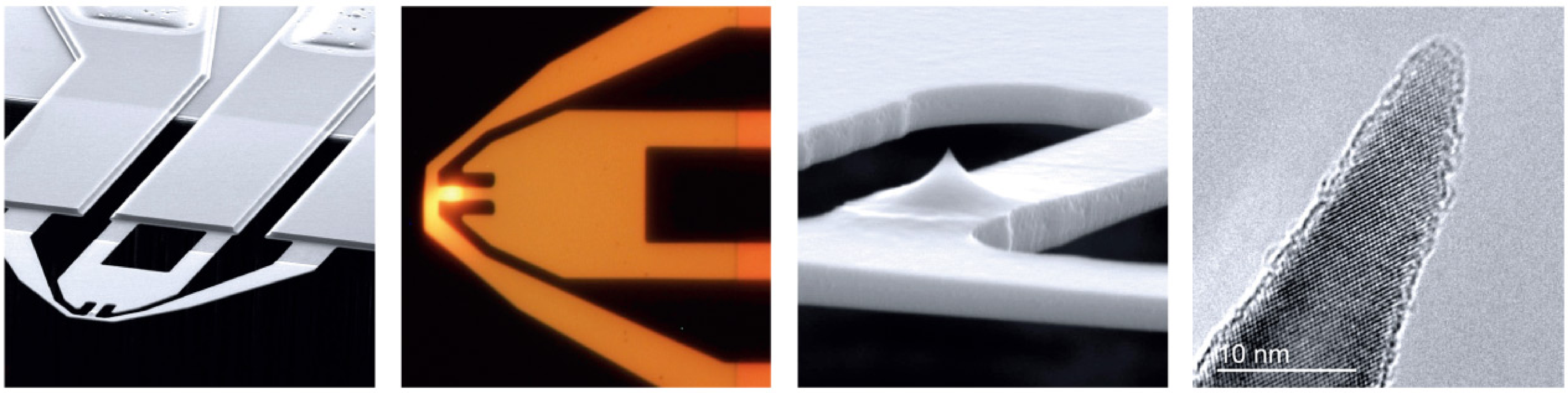
The NanoFrazor® Scholar is an entry-level nanopatterning system with many unique capabilities. It is particularly well-suited for academic research groups as a simple tool to easily create their own high-quality nanopatterns and devices.

NanoFrazor lithography systems are based on thermal scanning probe lithography. Core of the NanoFrazor® technology is an ultra-sharp heatable probe tip which is used for writing and simultaneous inspection of complex nanostructures. The heated tip creates arbitrary, high-resolution nanostructures by local sublimation of resists. Standard pattern transfer methods like lift-off or etching can be applied.




Patented "Closed-Loop Lithography" ensures high patterning accuracy

### NANOFRAZOR CANTILEVERS

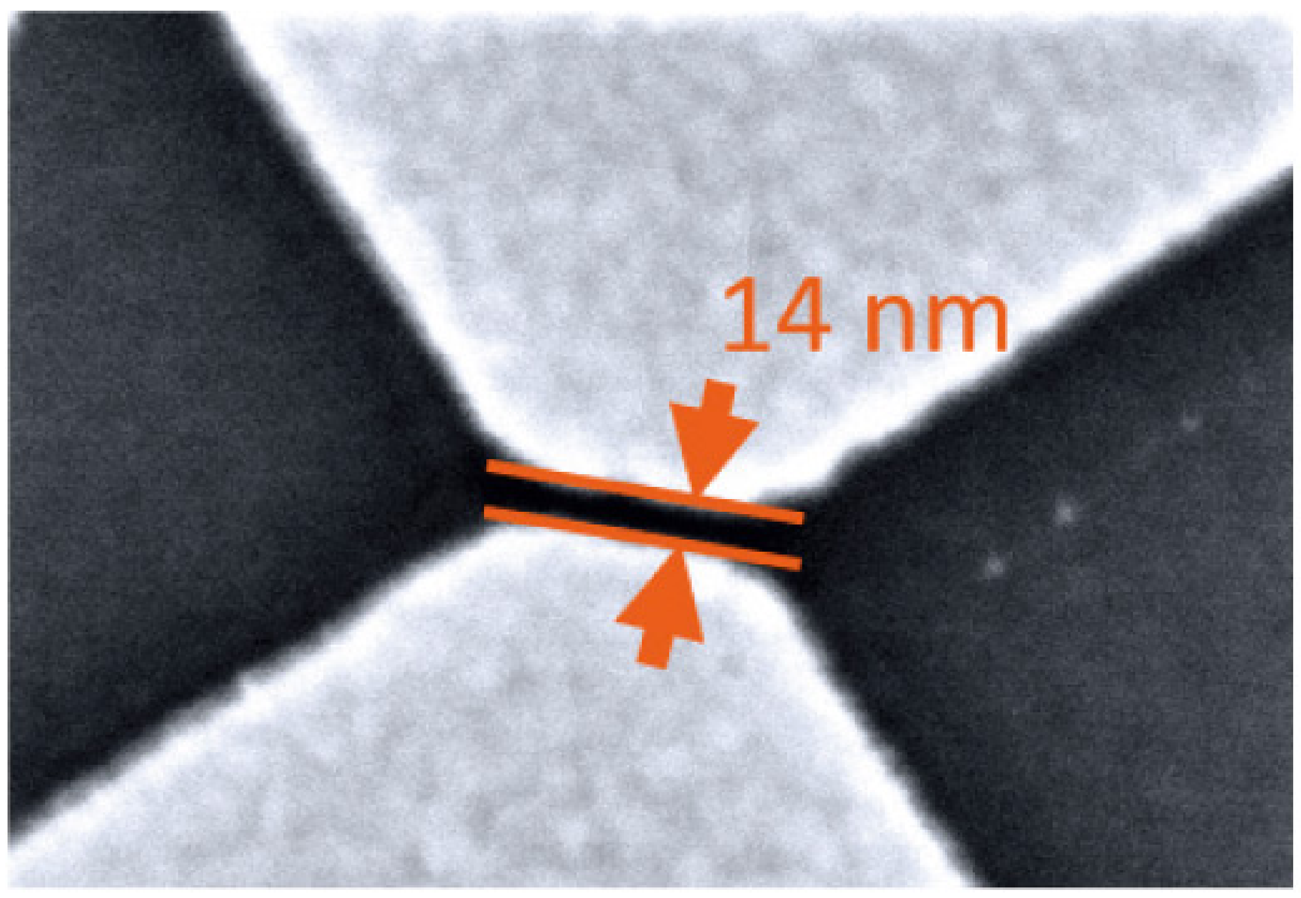


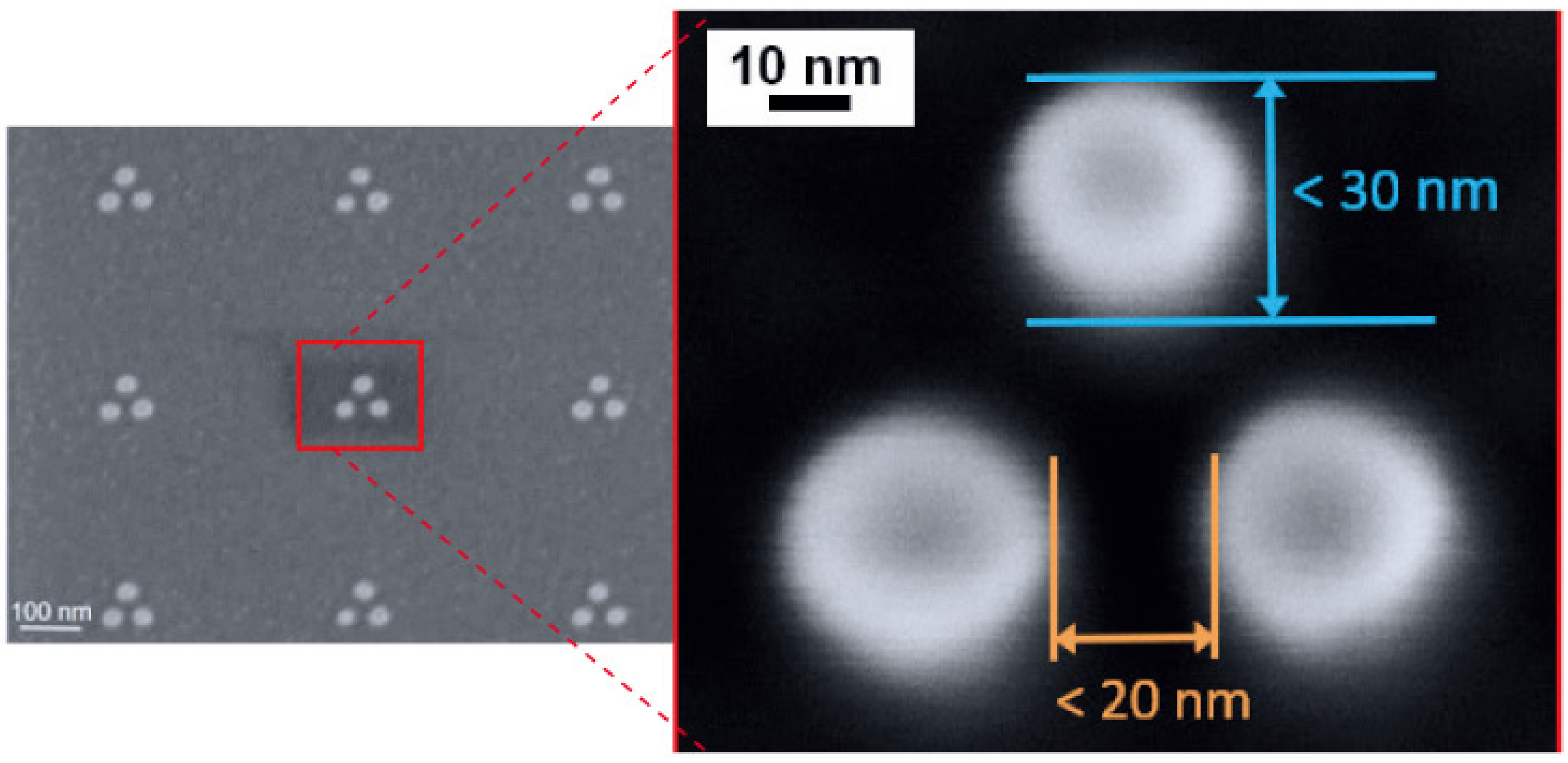

- Ultra-sharp Si tip
- Integrated tip heater
- Integrated force actuation
- Integrated topography sensor
- Fast exchange and calibration

### RAPID PROTOTYPING OF NANODEVICES

- Thermal probe lithography is the fastest of all scanning probe lithography methods (few µs exposure per pixel).
- Direct resist removal and in-situ inspection enable fast turn-around times.
- Detection of features buried under resist (e.g. 2D material flakes, nanowires, ...) for quick and accurate overlay of electrodes.

## ULTRA-HIGH RESOLUTION




Gap between two metal electrodes made with a simple lift-off process

Trimers etched into gold

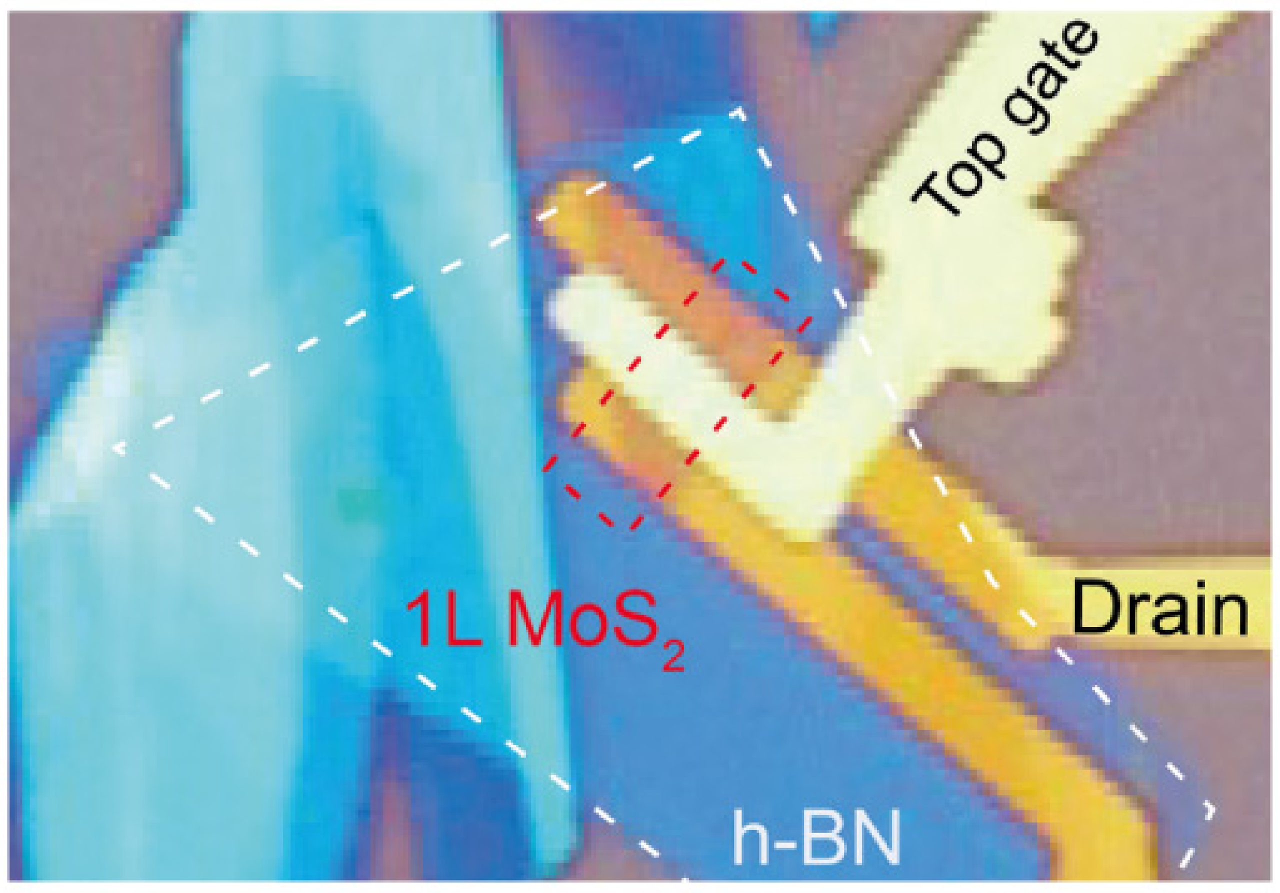
## NANOPATTERNING OF SENSITIVE MATERIALS AND DEVICES

### NANOFRAZOR LITHOGRAPHY

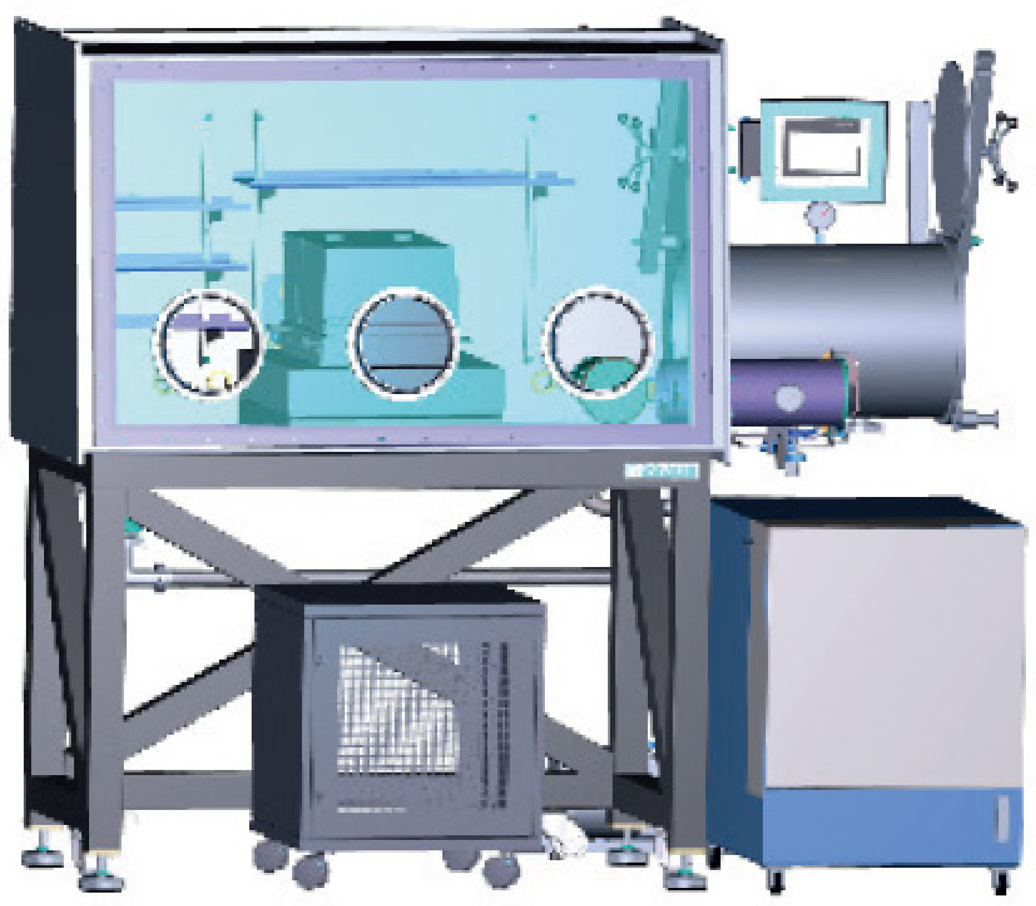
The tip heats the top resist layer only. Material below the resist (e.g. 2D materials, topological insulators, nanowires, etc) remain completely unharmed during patterning of the resist. The NanoFrazor® can be incorporated inside a glovebox. This facilitates nanolithography on samples that deteriorate in air.

### CHARGED-PARTICLE LITHOGRAPHY

Exposure to high-energy charged particles damages samples by unwanted creation & scission of covalent bonds, vacancies, trapped charges or lattice defects. Such defects deteriorate the device performance when using sensitive materials or designs.




$MoS_2$ top-gate transistors with record on/off ratios of $10^{10}$. Significantly less damage and resist residues compared to contacts made by EBL lead to vanishing Schottky barriers at the contacts.
Courtesy of Riedo group at NYU, see Zheng et al, Nat. Electronics 2019



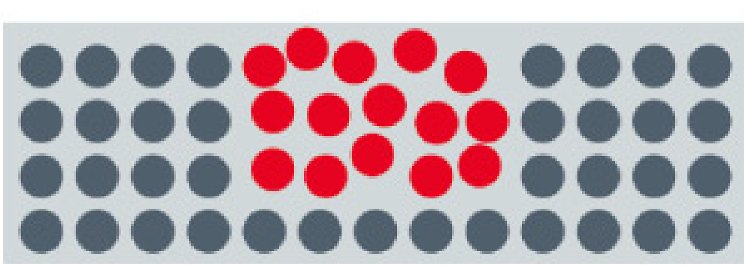
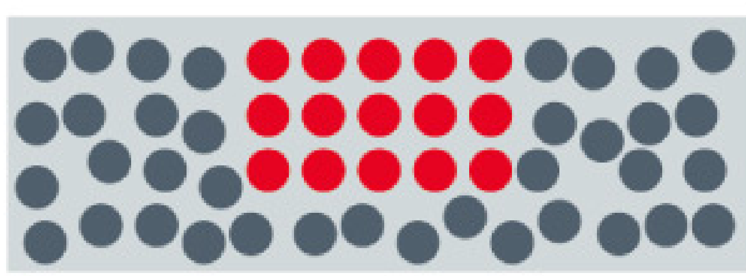
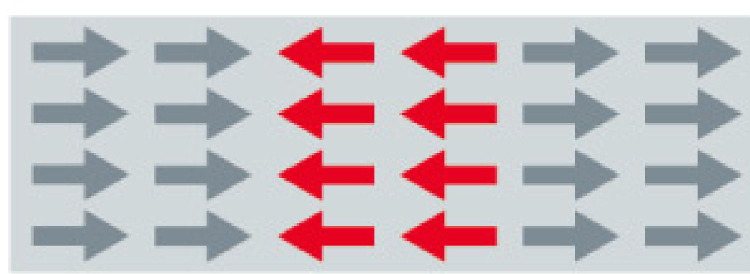
NanoFrazor Scholar inside a custom designed glovebox from MBraun

### NANOSCALE MATERIAL CONVERSION

The heated tip can alternatively be used to induce highly localized **modification of materials: Deprotection of functional groups,** precursor conversion, amorphization, crystallization, change of magnetic orientation, etc.

### OTHER UNIQUE CAPABILITIES

- **3D grayscale lithography** with unprecedented accuracy enabled by closed-loop lithography
- **Accurate overlay and stitching** without artificial markers, achieved by topography imaging

# NanoFrazor® Scholar

## SYSTEM SPECIFICATIONS

| Patterning performance | |
|---|---|
| Minimum structure size [nm] | 20 |
| Minimum lines and spaces [half pitch, nm] | 30 |
| Grayscale / 3D-resolution (step size in PPA) [nm] | 3 |
| Writing field size [X µm x Y µm] | 60 x 60 |
| Field stitching accuracy (markerless, using in-situ imaging) [nm] | 50 |
| Overlay accuracy (markerless, using in-situ imaging) [nm] | 50 |
| Write speed (typical scan speed) [mm/s] | 0.5 |
| Write speed (50 nm pixel) [$\mu m^2$/min] | 500 |

| Imaging performance | |
|---|---|
| Lateral imaging resolution (feature size) [nm] | 10 |
| Vertical resolution (topography sensitivity) [nm] | <0.5 |
| Imaging speed (@ 50 nm resolution) [$\mu m^2$/min] | 500 |

| System features | |
|---|---|
| Substrate sizes | 1 x 1 $mm^2$ to 100 x 100 $mm^2$<br>Thickness: 5 mm with optical access, 10 mm without optical access |
| Optical microscope | 0.6 µm digital resolution, 2.4 µm diffraction limit, 1.0 mm x 1.0 mm field of view |
| Magnetic cantilever holder | Fast (< 1 min) and accurate tip exchange |
| Housing | Compact housing with separate controller rack, active vibration isolation |
| Software features | GDS and bitmap import, topography image analysis and drawing for overlay, fully automated calibration routines, Python scripting |

| NanoFrazor cantilever features | |
|---|---|
| Integrated components | Tip heater, topography sensor, electrostatic actuation |
| Tip geometry | Conical tip with < 10 nm radius and 750 nm length |
| Tip heater temperature range | 25 °C – 1100 °C (< 1 K setpoint resolution) |

| System dimensions & installation requirements | |
|---|---|
| Height × width × depth | Table top: 40 cm x 40 cm x 45 cm, electronic trolley: 66 cm x 56 cm, x 60 cm |
| Weight | 100 kg |
| Power input | 1 x 110 or 220 V AC, 10 A |
| Vibration and noise level | Ambient acoustic noise levels need to be kept below 40 dB for best performance. A strong table is required. Floor requires vibration level VC-B. |

| Other considerations |
|---|
| Recipe book with detailed descriptions of various processes is available (regularly updated with software). |
| Cantilever tips degrade over time (> 50 h patterning possible). Exchange is fast and low cost for tool owners. |
| A cleanroom or special laboratory is not required. No vacuum needed. |
| Unique capabilities make it easy to receive government funding (for system itself or later research projects). |

**Please note:** Specifications depend on individual process conditions and may very according to equipment configuration.
Write speed depends on exposure area. Design and specifications are subject to change without prior notice.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